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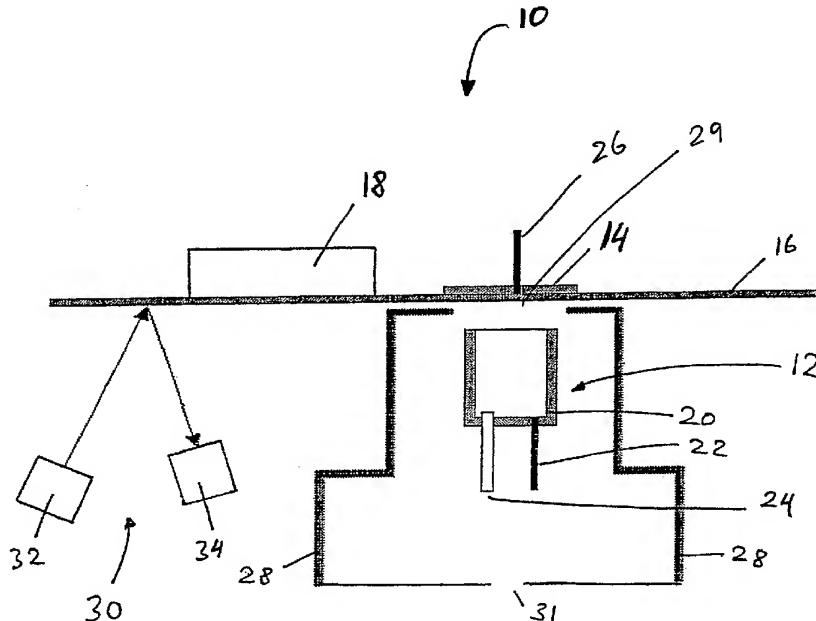
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(54) Title: AN APPARATUS FOR PLASMA TREATMENT



(57) Abstract: The present invention provides an apparatus (10) for plasma treatment of a substrate surface (16). The apparatus comprises a plasma source (12) for generating a plasma and a plasma-control electrode (14). The apparatus further comprises a drive means for effecting a relative movement between the plasma-control electrode (14) and the plasma source (12) or of the plasma-control electrode (14) and the plasma source (12) relative to the substrate (16). The plasma-control electrode (14) is located adjacent to the substrate (16) to facilitate treatment of the substrate surface (16) in a controlled manner.

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